

FORM PTO-1449		Atty. Docket No.: M61.12-0379	Appl. No.: 09/823,580
<p style="text-align: center;">LIST OF PATENTS AND PUBLICATIONS FOR APPLICANT'S INFORMATION DISCLOSURE STATEMENT</p> <p style="text-align: right;">O I P E NOV 12 2004 PATENT & TRADEMARK OFFICE U.S. C. P. A.</p>		First Named Inventor: Joshua T. Goodman et al.	
		Filing Date	Group Art:
		March 31, 2001	2151

U.S. PATENT DOCUMENTS

Examiner Initial	Document No.	Date	Name	Class	Sub Class	Filing Date If Appropriate
JW	AA	5,627,980	Schilit et al.	395	353	
JW	AB	5,818,437	Grover et al.	345	326	
JW	AC	5,953,541	King et al.	395	887	
JW	AD	6,002,390	Masui	345	173	
JW	AE	6,011,544	Sato	345	168	
JW	AF	6,169,538	Nowlan et al.	345	168	
JW	AG	6,271,835	Hoeksma	345	168	
JW	AH	6,741,235	Goren	345	173	
JW	AI	6,782,357	Goodman et al.	704	9	
JW	AJ	US2002/0126097 A1	Savolainen	345	168	
JW	AK	US2002/0180689 A1	Venolia	345	156	
JW	AL	US2003/0011574 A1	Goodman	345	172	
JW	AM	US2003/0023420 A1	Goodman	704	1	

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

JW	AN	F. Jelinek, "Self Organized Language Modeling for Speech Recognition", Language Processing for Speech Recognition, pp. 450-503.
JW	AO	K. Seymore et al., "Scalable Backoff Language Models", In Proc. ICSLP, Vol. 1, pp. 232-235, Philadelphia, 1996.
JW	AP	Stolcke, "Entropy-based Pruning of Backoff Language Models", Proc. DRAPA News Transcription and Understanding Workshop, pp. 270-274, Lansdowne, VA.
JW	AQ	Chen et al., "An Empirical Study of Smoothing Techniques for Language Modeling", TR-10-98, Computer Science Group, pp. 1-64, Harvard University, 1998.
JW	AR	Lehikoinen et al., "BinScroll: A Rapid Selection Technique for Alphanumeric Lists", CHI 2000, pp. 261-262, April 1-6, 2000.
JW	AS	Ahlberg et al., "The Alphaslider: A Compact and Rapid Selector", Proc. CHI 94, p. 365-371.

EXAMINER:

DATE CONSIDERED: 11/17/05

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.